Supplementary Materials

Enhancing the photoelectric performance of metal oxide semiconductors by

introduction of dislocations

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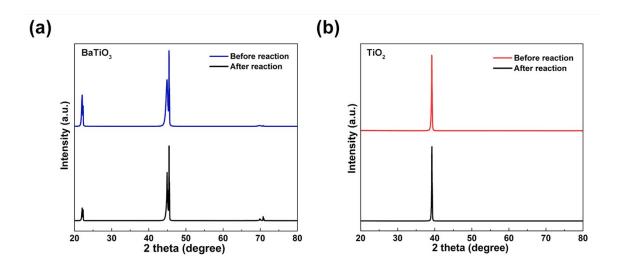


Figure S1. The XRD spectra comparation of a) $BaTiO_3$ (001) dislocation sample and b) TiO_2 (100) dislocation sample before and after reaction, respectively.

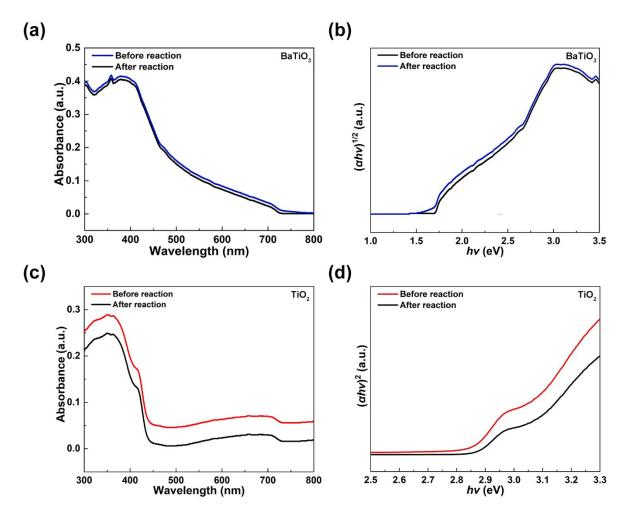


Figure S2. The UV-vis light absorbance spectra comparation of a) $BaTiO_3$ (001) dislocation sample and c) TiO_2 (100) dislocation sample and their corresponding bandgap Tauc plots of b) $BaTiO_3$ (001) dislocation sample and d) TiO_2 (100) dislocation sample before and after three consecutive runs, respectively.